

## Electronic Supplementary Information

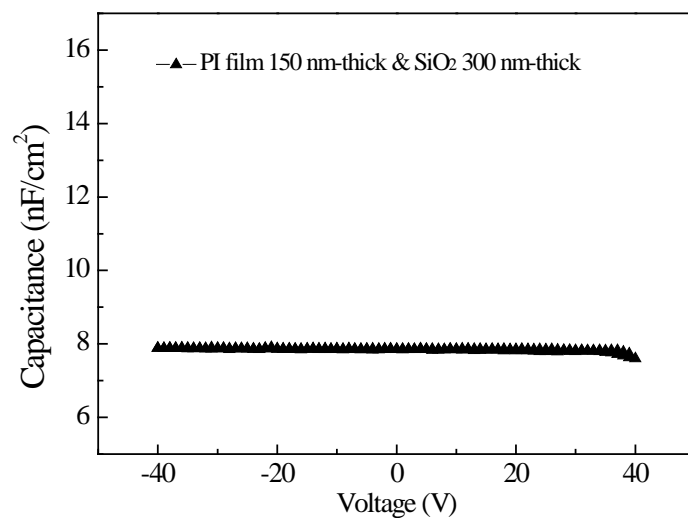
### Memory characteristics of organic field-effect memory transistors modulated by nano-p-n junctions

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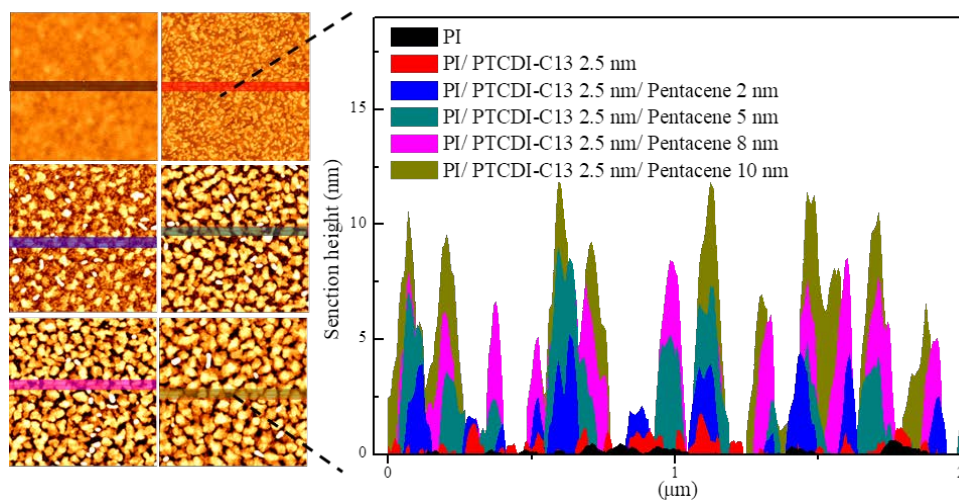
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**Fig. S1** The capacitances of PI/SiO<sub>2</sub>/Si gate dielectrics measured at frequencies of 1 kHz.



**Fig. S2** The AFM images (left column) and related cross-section analyses (right column) of the pentacene films deposited onto PI/submonolayer PTCDI-C13.